

14 May 2004

Updated Search

09/809,295

L Number	Hits	Search Text	DB	Time stamp
1	29	((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane) and ((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (plating or electroplat\$3 or electrodeposit\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 14:49
2	8	("4874476" "4919769" "5013415" "5262193" "5702583" "5997712" "6179982" "6258244").PN.	USPAT	2004/05/14 16:05
3	29	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane) and ((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (plating or electroplat\$3 or electrodeposit\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 14:50
4	109	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane) and ((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 14:52
5	132	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane) and (((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 15:54
7	1	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane) and (((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 14:58
6	46	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane) and (((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 14:54
8	8	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane) and (((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 15:04
9	389	((204/\$.ccls. or 205/\$.ccls.) and (degas\$5 or "de-gas" or "de-gassed" or "de-gassing")) and membrane) and (((204/\$.ccls. or 205/\$.ccls.) and (degas\$5 or "de-gas" or "de-gassed" or "de-gassing")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 15:03
10	21	((204/\$.ccls. or 205/\$.ccls.) and (degas\$5 or "de-gas" or "de-gassed" or "de-gassing")) and membrane) and (((204/\$.ccls. or 205/\$.ccls.) and (degas\$5 or "de-gas" or "de-gassed" or "de-gassing")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 15:06

11	1459	(204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$5 or "de-gas" or "de-gassed" or "de-gassing")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 16:00
12	154	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$5 or "de-gas" or "de-gassed" or "de-gassing")) and (pump with control\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 15:56
13	68	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$5 or "de-gas" or "de-gassed" or "de-gassing")) and (pump with control\$5)) and membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 15:55
15	10	((204/\$.ccls. or 205/\$.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$5 or "de-gas" or "de-gassed" or "de-gassing")) and ((pump with control\$5) same membrane)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 16:00
16	142	(96/6,156.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$5 or "de-gas" or "de-gassed" or "de-gassing")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 16:00
17	3	((96/6,156.ccls.) and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$5 or "de-gas" or "de-gassed" or "de-gassing")) and ((pump with control\$5) same membrane)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/14 16:00
18	1	((("4874476" "4919769" "5013415" "5262193" "5702583" "5997712" "6179982" "6258244").PN.) and membrane	USPAT	2004/05/14 16:05
19	3	((("4874476" "4919769" "5013415" "5262193" "5702583" "5997712" "6179982" "6258244").PN.) and (degas or deaerat\$5)	USPAT	2004/05/14 16:06
20	4	((("4874476" "4919769" "5013415" "5262193" "5702583" "5997712" "6179982" "6258244").PN.) and (degas\$6 or deaerat\$5)	USPAT	2004/05/14 16:06
-	1	809295.apn.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 10:30
-	224	204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:31
-	99	(204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 11:47
-	25	(204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and diaphragm	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 11:52

-	132	(204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (plating or plate or plated or electroplat\$3 or electrodeposit\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 11:53
-	18	((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and diaphragm) and ((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (plating or plate or plated or electroplat\$3 or electrodeposit\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 11:53
-	63	(204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (plating or plated or electroplat\$3 or electrodeposit\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 12:00
-	9	((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and diaphragm) and ((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (plating or plated or electroplat\$3 or electrodeposit\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 11:59
-	33	((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and membrane) and ((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (plating or plated or electroplat\$3 or electrodeposit\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 11:59
-	53	(204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (plating or electroplat\$3 or electrodeposit\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:32
-	4896	204/228.1,228.6,232,237,238,242,252,263,264,266,275,276,278.ccls	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 12:06
-	26	204/228.1,228.6,232,237,238,242,252,263,264,266,275,276,278.ccls and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")	US-PGPUB; EPO; JPO; DERWENT	2003/05/28 12:26
-	1	US-20030057104-A1.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 13:51
-	2	JP-2001297744-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 12:29
-	1	2001JP-2001-297744	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 12:29
-	0	204/\$.ccls and (semiconductor or wafer) and diaphragm	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:24

-	274	204/\$.ccls. and (semiconductor or wafer) and diaphragm	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:25
-	1	(204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated")) and (204/\$.ccls. and (semiconductor or wafer) and diaphragm)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:26
-	24	(204/\$.ccls. and (semiconductor or wafer) and diaphragm) and (remov\$3 near (gas or oxygen or "o.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:35
-	8	(204/\$.ccls. and (semiconductor or wafer) and diaphragm) and degas\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:30
-	28	((204/\$.ccls. and (semiconductor or wafer) and diaphragm) and (remov\$3 near (gas or oxygen or "o.sub.2"))) ((204/\$.ccls. and (semiconductor or wafer) and diaphragm) and degas\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:31
-	1016	204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:31
-	166	(204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$4)) and (plating or electroplat\$3 or electrodeposit\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:32
-	22	((204/\$.ccls. and (deaerat\$3 or "de-aerate" or "de-aerating" or "de-aerator" or "de-aerated" or degas\$4)) and (plating or electroplat\$3 or electrodeposit\$3)) and diaphragm	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:32
-	37	(204/\$.ccls. and (semiconductor or wafer) and diaphragm) and ((remov\$3 or purg\$3) near (gas or oxygen or "o.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:38
-	13	((204/\$.ccls. and (semiconductor or wafer) and diaphragm) and ((remov\$3 or purg\$3) near (gas or oxygen or "o.sub.2"))) not (((204/\$.ccls. and (semiconductor or wafer) and diaphragm) and (remov\$3 near (gas or oxygen or "o.sub.2")))) ((204/\$.ccls. and (semiconductor or wafer) and diaphragm) and degas\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 14:38
-	97	204/\$.ccls. and (semiconductor or wafer) and seal and diaphragm	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 16:15
-	39	(204/\$.ccls. and (semiconductor or wafer) and seal and diaphragm) and (plating or electroplat\$3 or electrodeposit\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 09:44

-	36	((204/\$.ccls. and (semiconductor or wafer) and seal and diaphragm) and (plating or electroplat\$3 or electrodeposit\$3)) not (diaphragm adj pump)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 16:24
-	24	((((204/\$.ccls. and (semiconductor or wafer) and seal and diaphragm) and (plating or electroplat\$3 or electrodeposit\$3)) not (diaphragm adj pump)) not (finger adj diaphragm)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 16:28
-	34	(204/\$.ccls. and (semiconductor or wafer) and seal and diaphragm) and (bubble or deaerat\$3 or degas\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/28 16:29
-	125	204/\$.ccls. and (((wafer or substrate) near holder) same seal)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 09:35
-	4	204/\$.ccls. and YOSHIOKA.in. and JUNICHIRO.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 09:43
-	235	204/\$.ccls. and (wafer or semiconductor) and ((oxygen or "o.sub.2") near (sensor or detector))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 09:44
-	49	(204/\$.ccls. and (wafer or semiconductor) and ((oxygen or "o.sub.2") near (sensor or detector))) and (plating or electroplat\$3 or electrodeposit\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 09:45
-	2	jp-11078564-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 10:32
-	4	us-6454918-b1.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 11:14
-	1	2001-338100.NRAN.	DERWENT	2003/05/29 10:33
-	52	degasser same (membrane and vacuum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 11:15
-	27	degasser same (membrane and vacuum and pump)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 11:16
-	7	degasser same (membrane and (vacuum near pump))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/29 11:45

-	1253	204/\$.ccls. and (control\$5 near3 pump)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/16 09:43
-	56	204/\$.ccls. and (control\$5 near3 pump with (speed or rotation))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/16 09:43